

1. Record Nr.	UNINA9910872956003321
Titolo	1998 3rd International Symposium on Plasma Process-Induced Damage : June 4-5, 1998, Honolulu, Hawaii, USA
Pubbl/distr/stampa	[Place of publication not identified], : Northern California Chapter of the American Vacuum Society, 1998
Disciplina	621.3815/2
Soggetti	Semiconductor wafers - Defects Semiconductors - Effect of radiation on Plasma etching Electrical & Computer Engineering Engineering & Applied Sciences Electrical Engineering
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Bibliographic Level Mode of Issuance: Monograph